

BEAMeeting E-Beam & Laser Workshop Technical Workshop & Discussion				
SESSION	BEAMeeting - Tuesday, May 28	Pacific	Eastern	CET
Ulrich Hofmann GenISys	Welcome & Introduction GenISys Update	9:00 am	12:00 pm	18:00
Nezih Unal GenISys	Laser Simulation and Process Calibration	9:20 am	12:20	18:20
Bethany Niedzielski Huffman MIT Lincoln Lab	Quantum Computing and Electron Beam Lithography	9:40 am	12:40	18:40
Marvin Zai GenISys	Building Bridges in Beamer with 3D Edge PEC	10:00 am	1:00	19:00
Bernadeta Srijanto Oak Ridge National Laboratory	Maximizing process efficiency with dual current exposure strategy	10:20 am	1:20	19:20
	Coffee Break	10:30 am	1:30	19:30
Sven Bauerdick GenISys	Unveiling the NEW InSPEC	10:50 am	1:50	19:50
Leonidas E. Ocola IBM	<i>"So you think you know eta in PEC ..."</i>	11:10 am	2:10	20:10
Dengyang Lu University of Pennsylvania	Image processing and Data Preparation for Structural Color Generation	11:30 am	2:30	20:30
Roberto Panepucci Cornell NanoScale Facility	Distortion Correction and Application	11:50 am	2:50	20:50
	Lunch	12:10 pm	3:10	21:10
Chad Eichfeld Penn State University	Automated SEM Metrology Use Cases for InSPEC	1:00 pm	4:00	22:00
Benedikt Stender Heidelberg Instruments	MPO 100: The Future of 3D Nano- and Micro-Lithography	1:20 pm	4:20	22:20
Kaustubh Vyas GenISys	Radial PEC, Powerful Filter & the new Fields module	1:40 pm	4:40	22:40
	Coffee Break	2:00 pm	5:00	23:00
Sven Bauerdick GenISys	ProSEM vs. InSPEC: the "best" metrology solution	2:20 pm	5:20	23:20
Nezih Unal GenISys	What's New in BEAMER Roadmap Discussion	2:30 pm	5:30	23:30
	FINAL Closing	3:00 pm	6:00	24:00